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Patent  
USSN.09/375,627  
Atty Docket 99108

1756  
#3/a  
8/35/00  
✓ Short

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

HANS LOSCHNER et al.

For: PARTICLE MULTIBEAM LITHOGRAPHY

Serial No. 09/375,627

Filed: August 17, 1999

Group Art Unit:  
1756

Examiner  
Chris Young

RECEIVED  
AUG 10 2000  
MAIL ROOM

PRELIMINARY AMENDMENT BEFORE ACTION

TO:  
Assistant Commissioner of Patents  
Washington, D.C. 20231

RECEIVED

AUG 15 2000

TECHNOLOGY CENTER 2300

Dear Sir:

Applicant requests that the subject application be amended as follows  
before action:

IN THE CLAIMS:

Please amend claim 19 as set forth below:

19. (Amended) A method for multibeam lithography by means of electrically charged particles using the apparatus of claim 1, wherein a particle beam is produced by a particle source, transferred into an illuminating beam and formed into a plurality of sub-beams, the sub-beams being formed by means of at least one aperture plate having an array of a corresponding plurality of apertures and the sub-beams are focused onto the surface of a substrate, and wherein the beam position of each sub-beam is controlled by means of a deflection unit, for correcting individual imaging aberrations of the respective sub-beam with respect to the desired target position and/or positioning the sub-beam during a writing process [an] on the substrate surface.

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